

<b>Notice of References Cited</b>		Application No. <b>08/889,440</b>	Applicant(s) <b>Takeuchi et al.</b>		
		Examiner <b>Hugh Jones</b>	Group Art Unit <b>2763</b>	Page 1 of 1	

**U.S. PATENT DOCUMENTS**

	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS
A	5,421,934	06/95	Misaka et al.	216	59
B	5,751,607	05/98	Ohta	364	578
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F					
G					
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J					
K					
L					
M					

**FOREIGN PATENT DOCUMENTS**

	DOCUMENT NO.	DATE	COUNTRY	NAME	CLASS	SUBCLASS
N						
O						
P						
Q						
R						
S						
T						

**NON-PATENT DOCUMENTS**

	DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
U	F. H. Baumann et al., "3D Modeling of Sputter and Reflow Processes for Interconnect Metals," IEDM 95, pg. 4.4.1-4.4.4	1995
V	T. Takagi, "Development of New Materials by Ionized-Cluster Beam Technique," Mat. Res. Soc. Symp. Proc. Vol. 27, pg. 501-511	1987
W	H. M. Jones et al., "Monte Carlo Investigation of Electron-Impact Ionization in Liquid Xenon," Phys. Rev. B. vol. 48, pg. 9382-9387	1993
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